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Li-Da Huang, Martin D. F. Wong

 June 2004 **Proceedings of the 41st annual conference on Design automation**

Publisher: ACM Press

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As the technology migrates into the deep submicron manufacturing(DSM) era, the critical dimension of the circuits is getting smaller than the lithographic wavelength. The unavoidable light diffraction phenomena in the sub-wavelength technologies have become one of the major factors in the yield rate. Optical proximity correction (OPC) is one of the methods adopted to compensate for the light diffraction effect as a post layout process. However, the process is time-consuming and the results are st ...

Keywords: OPC, VLSI, manufacturing, maze routing, micro-lithography, optical system

2 [Subwavelength lithography and its potential impact on design and EDA](#)



Andrew B. Kahng, Y. C. Pati

 June 1999 **Proceedings of the 36th ACM/IEEE conference on Design automation**

Publisher: ACM Press

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3 [Subwavelength optical lithography: challenges and impact on physical design](#)



A. B. Kahng, Y. C. Pati

 April 1999 **Proceedings of the 1999 international symposium on Physical design**

Publisher: ACM Press

 Full text available: [pdf\(1.30 MB\)](#) Additional Information: [full citation](#), [references](#), [citations](#), [index terms](#)

4 [Impact of RET on physical layouts](#)



Franklin M. Schellenberg, Luigi Capodiec

 April 2001 **Proceedings of the 2001 international symposium on Physical design**

Publisher: ACM Press



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IEEE STD IEEE Standard

1. High accurate optical proximity correction under the influences of lens aberration and illumination non-uniformity

Harazaki, K.; Hasegawa, Y.; Shichijo, Y.; Tabuchi, H.; Fujii, K.;
Microprocesses and Nanotechnology Conference, 2000 International
11-13 July 2000 Page(s):14 - 15

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3. **Multilevel full-chip gridless routing considering optical proximity correction**
Tai-Chen Chen; Yao-Wen Chang;

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